



PATENT  
Customer No. 22,852  
Attorney Docket No. 08137.0004-00000

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: )

Hiroshi SHINRIKI et al. )

Serial No.: 09/657,627 )

Filed: September 8, 2000 )

For: THIN FILM FORMING METHOD )  
AND THIN FILM FORMING )  
APPARATUS )

Group Art Unit: 1762

Examiner: B. Chen

#8/a  
Hyda  
12/30/01

Assistant Commissioner for Patents  
Washington, DC 20231

Sir:

RECEIVED  
DEC 27 2001  
TC 1700

AMENDMENT

In reply to the Office Action dated June 20, 2001, the period for reply having been extended for three months by a request for extension and fee payment filed concurrently herewith, please amend the application as follows:

IN THE TITLE:

Please change the title to read ☒ METHOD OF FORMING A THIN FILM--.

IN THE CLAIMS:

Please cancel claim 7 without prejudice or disclaimer, amend claims 1-6, 8, and 9, and add new claims 12 and 13, as follows:

LAW OFFICES  
FINNEGAN, HENDERSON  
FARABOW, GARRETT  
& DUNN, L.L.P.  
1300 I STREET, N.W.  
WASHINGTON, DC 20005  
202-408-4000

✓ 1. (Amended) A method of forming a thin film on a substrate in a reactor comprising a side having a shower head with a plurality of nozzles and a separate discharge nozzle, the method comprising:

42

a